

Quantum-Dot/Quantum-Well Mixed-Mode Infrared Photodetectors

**Research Center for Applied Sciences, Academia Sinica, Taiwan
Shih-Yen Lin**



Outline



➤ **Introductions**

- Quantum-Dot Infrared Photodetectors (QDIPs) vs. Quantum-Well Infrared Photodetectors (QWIPs)

➤ **The Disadvantages of QDIPs**

- Why Quantum-Dot/Quantum-Well Mixed-Mode Infrared Photodetectors (MMIPs)

➤ **The Device Performances of the QD/QW MMIPs**

- Spectral Responses of the QD/QW MMIPs
- Transition Mechanisms of the QD/QW MMIPs

➤ **Conclusions**

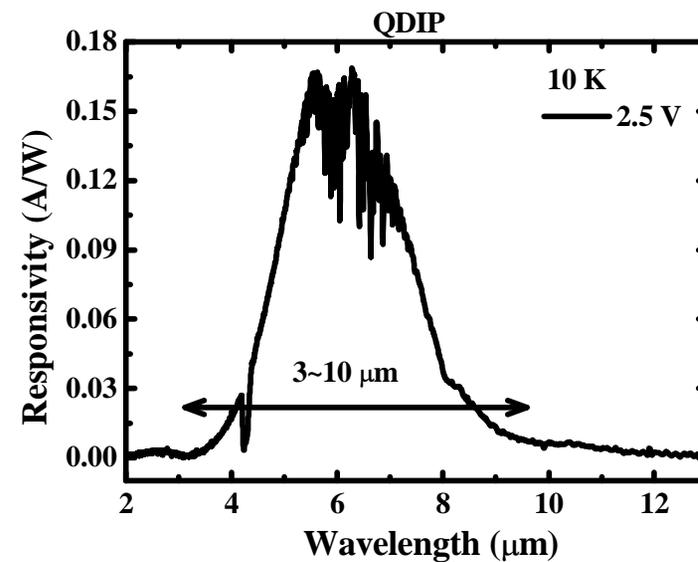
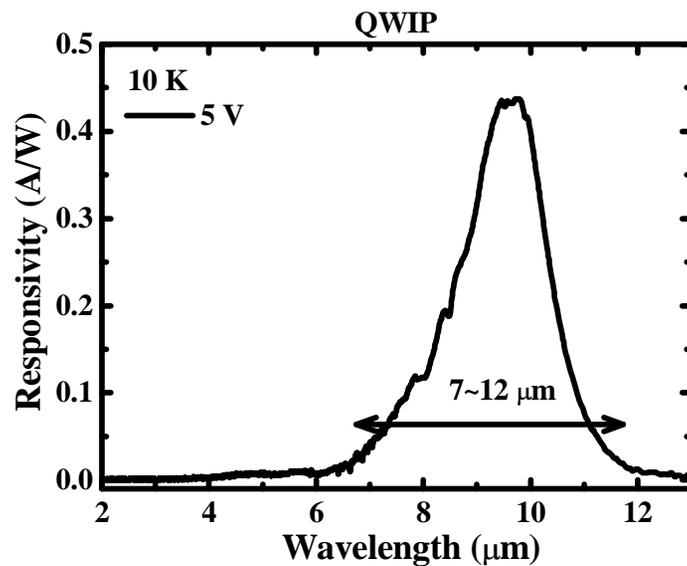
➤ **Future Work**



QDIPs vs. QWIPs



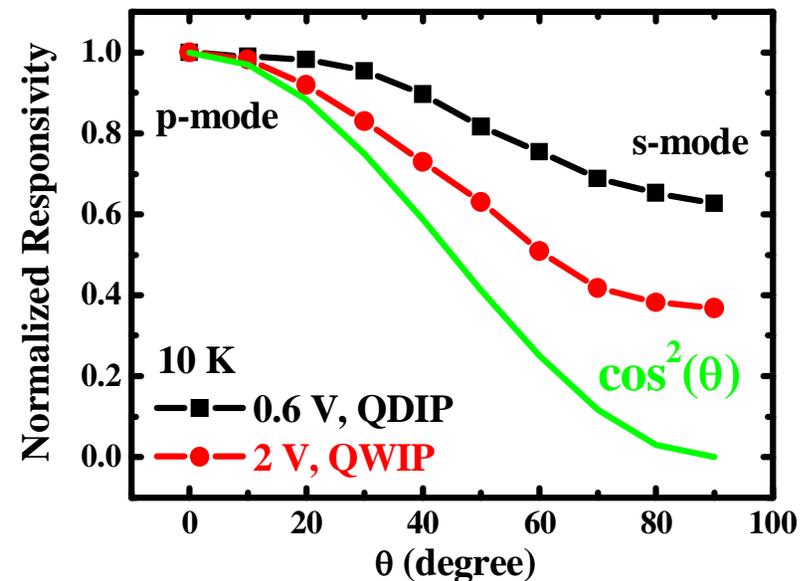
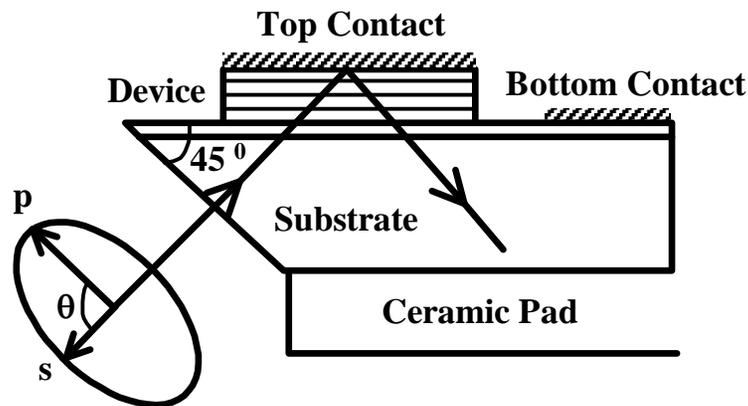
	QWIP	QDIP
	1 μm GaAs $n = 2 \times 10^{18} \text{ cm}^{-3}$	0.5 μm GaAs $n = 1 \times 10^{18} \text{ cm}^{-3}$
	30 nm $\text{Al}_{0.23}\text{Ga}_{0.77}\text{As}$ undoped	30 nm GaAs undoped
30 periods	6.6 nm GaAs $n = 5 \times 10^{17} \text{ cm}^{-3}$	2.4 ML InAs QD $n = 2 \times 10^{18} \text{ cm}^{-3}$
	30 nm $\text{Al}_{0.23}\text{Ga}_{0.77}\text{As}$ undoped	30 nm GaAs undoped
	1 μm GaAs $n = 2 \times 10^{18} \text{ cm}^{-3}$	1 μm GaAs $n = 1 \times 10^{18} \text{ cm}^{-3}$
	350 μm S-I GaAs Substrate	



Normal Incident Absorption



	QWIP	QDIP
	1 μm GaAs $n = 2 \times 10^{18} \text{ cm}^{-3}$	0.5 μm GaAs $n = 1 \times 10^{18} \text{ cm}^{-3}$
	30 nm $\text{Al}_{0.23}\text{Ga}_{0.77}\text{As}$ undoped	30 nm GaAs undoped
30 periods	6.6 nm GaAs $n = 5 \times 10^{17} \text{ cm}^{-3}$	2.4 ML InAs QD $n = 2 \times 10^{18} \text{ cm}^{-3}$
	30 nm $\text{Al}_{0.23}\text{Ga}_{0.77}\text{As}$ undoped	30 nm GaAs undoped
	1 μm GaAs $n = 2 \times 10^{18} \text{ cm}^{-3}$	1 μm GaAs $n = 1 \times 10^{18} \text{ cm}^{-3}$
	350 μm S-I GaAs Substrate	



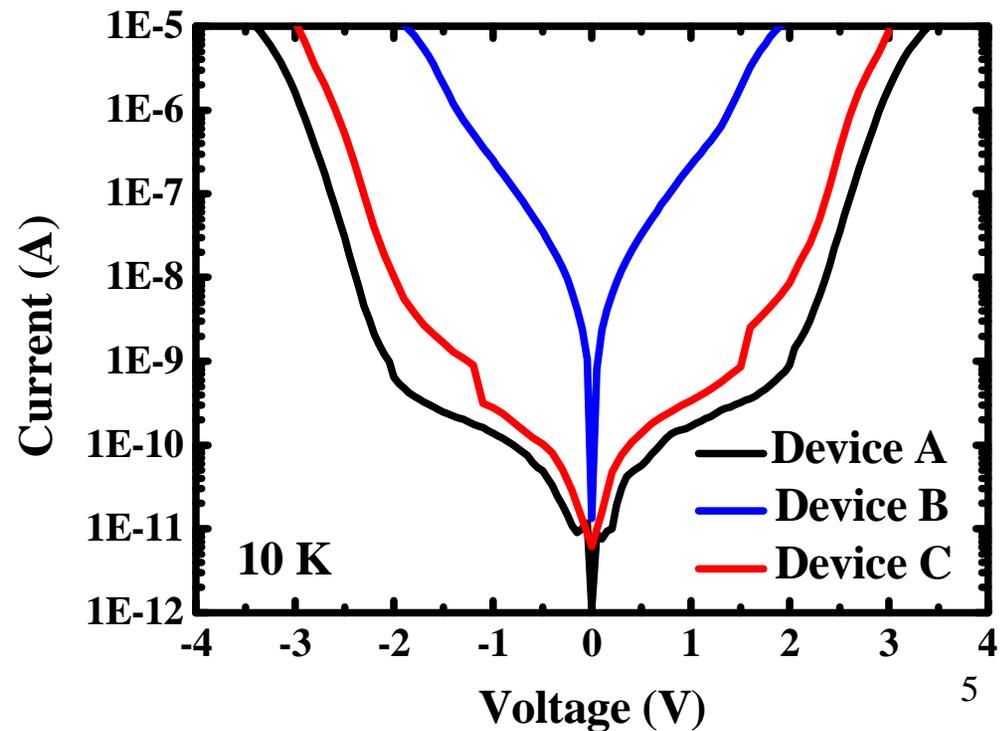


High-Temperature Operation



QDIP Samples	A	B	C
Top Contact	500 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$		
Barrier Layer	30 nm undoped GaAs		
30 x 2.4 ML InAs QDs (cm^{-3})	5×10^{17}	1×10^{18}	2×10^{18}
Bottom Contact	1000 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$		
Substrate	350 mm (100) Semi-Insulating GaAs		

➤ The dark currents of QDIPs would change significantly with the doping densities.



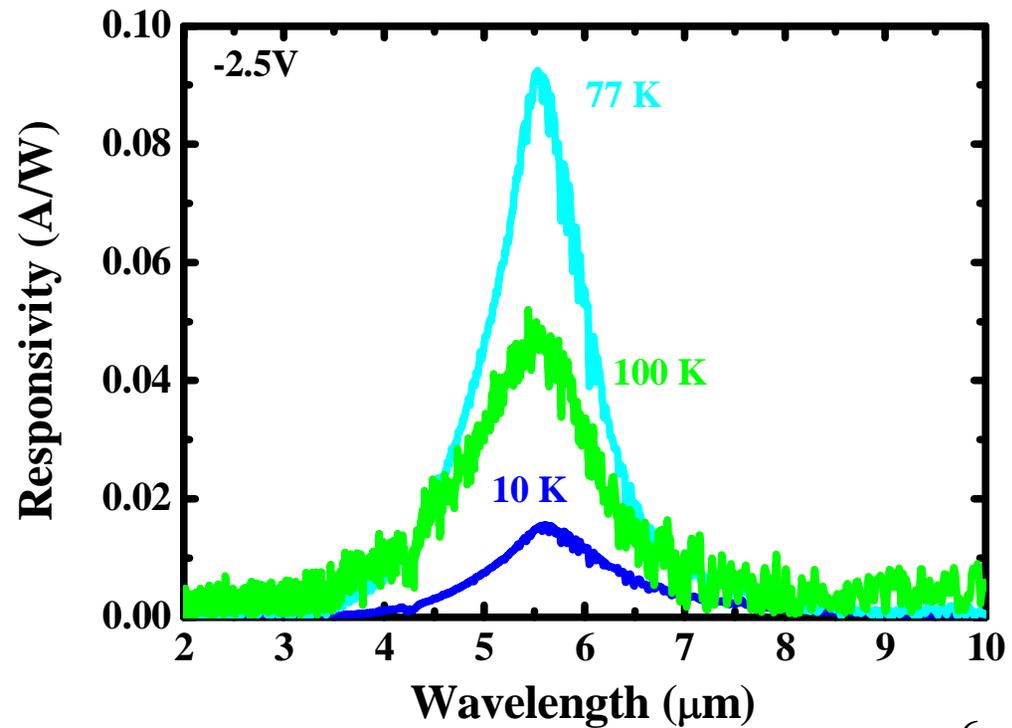


High-Temperature Operation



	Top Contact	1000 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$
15x	Barrier Layer	30 nm undoped GaAs
	2.4 ML InAs QDs	undoped
	Bottom Contact	1000 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$
	Substrate	350 mm (100) Semi-Insulating GaAs

➤ **Decreasing electron capture probability is responsible for the increasing photocurrent with increasing temperatures.**

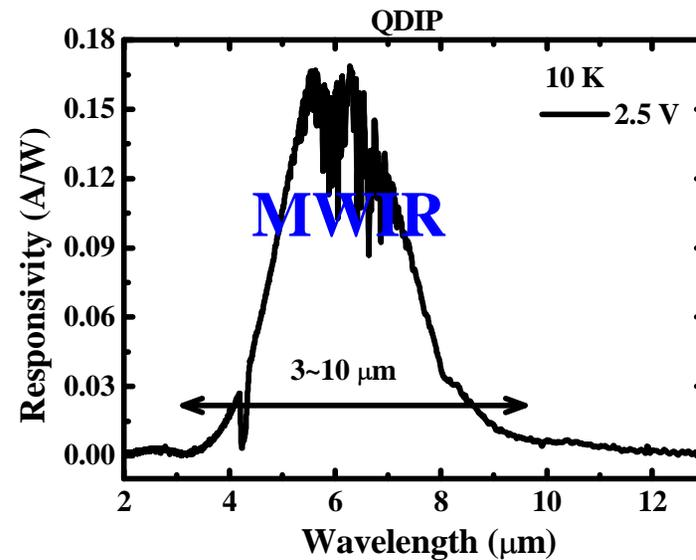
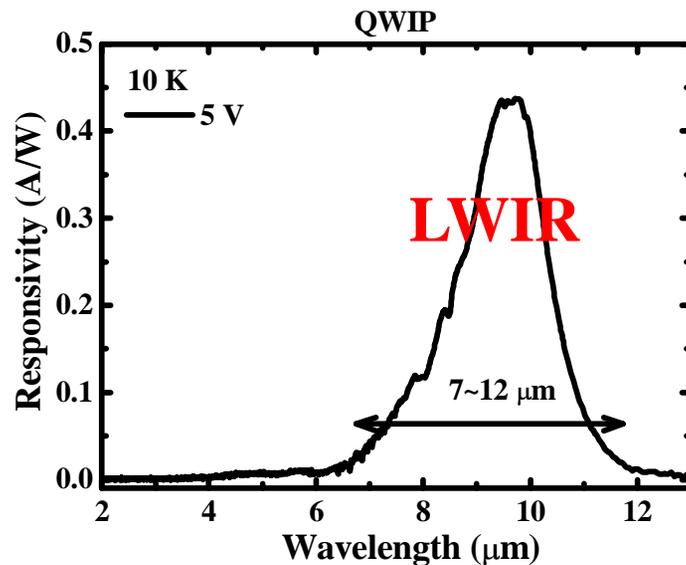




Why QD/QW MMIPs?



	QWIP	QDIP
	1 μm GaAs $n = 2 \times 10^{18} \text{ cm}^{-3}$	0.5 μm GaAs $n = 1 \times 10^{18} \text{ cm}^{-3}$
	30 nm $\text{Al}_{0.23}\text{Ga}_{0.77}\text{As}$ undoped	30 nm GaAs undoped
30 periods	6.6 nm GaAs $n = 5 \times 10^{17} \text{ cm}^{-3}$	2.4 ML InAs QD $n = 2 \times 10^{18} \text{ cm}^{-3}$
	30 nm $\text{Al}_{0.23}\text{Ga}_{0.77}\text{As}$ undoped	30 nm GaAs undoped
	1 μm GaAs $n = 2 \times 10^{18} \text{ cm}^{-3}$	1 μm GaAs $n = 1 \times 10^{18} \text{ cm}^{-3}$
	350 μm S-I GaAs Substrate	





Why QD/QW MMIPs?



- **Achieve MWIR and LWIR Detections within A Single Structure**
- **Maintain the High-Temperature Property of QDIPs**
- **Enhance Normal Incident Absorption for Both MWIR and LWIR Absorptions**



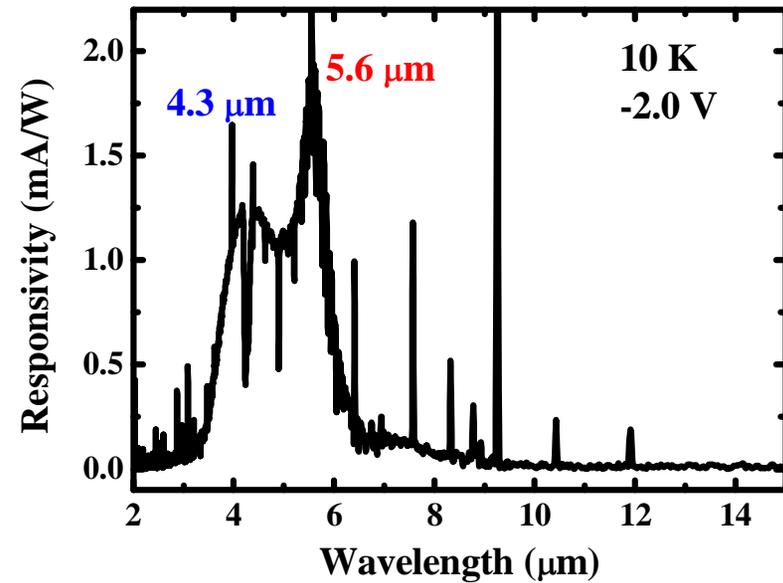
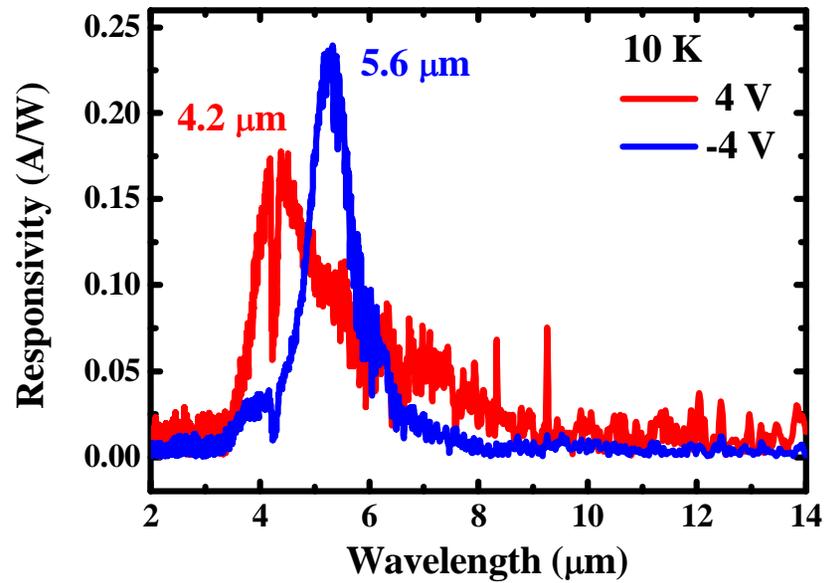
The QD/QW MMIP Device Structure



	Top Contact	300 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$
	25 nm $\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$	undoped
10x	8 nm GaAs (Doping=)	$n=5 \times 10^{17} \text{cm}^{-3}$
	2.4 ML InAs QDs	undoped
	1 nm GaAs	undoped
	25 nm $\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$	undoped
	Bottom Contact	600 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$
	Substrate	350 mm (100) Semi-Insulating GaAs



Spectral Responses of the MMIP





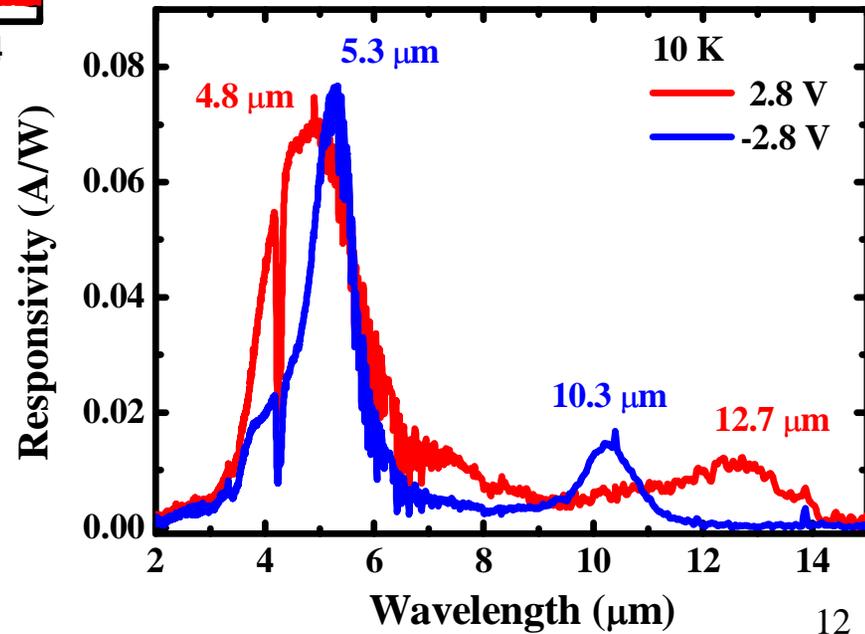
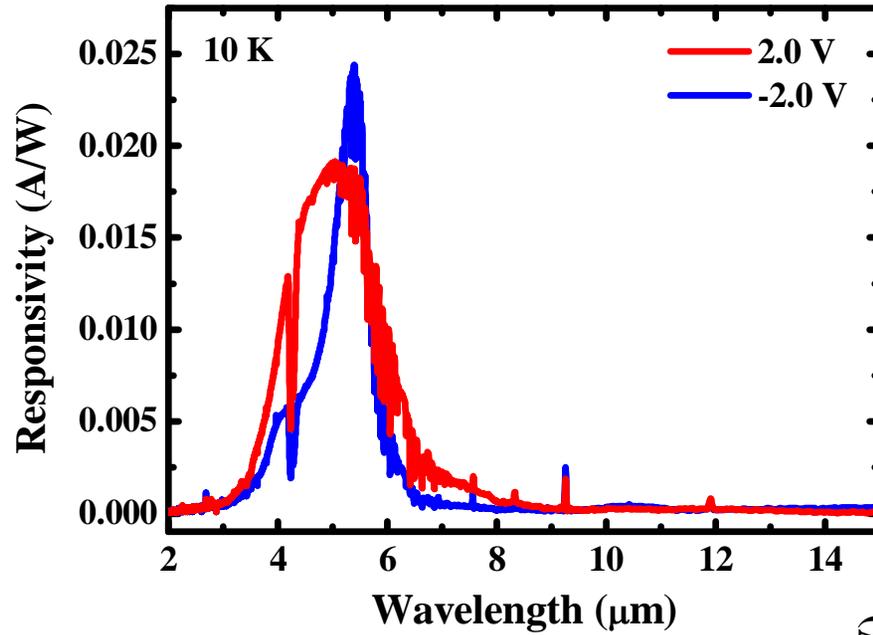
The QD/QW MMIP Device Structure



	Top Contact	300 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$
	25 nm $\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$	undoped
10x	8 nm GaAs (Doping=)	$n=1 \times 10^{18} \text{cm}^{-3}$
	2.4 ML InAs QDs	undoped
	1 nm GaAs	undoped
	25 nm $\text{Al}_{0.2}\text{Ga}_{0.8}\text{As}$	undoped
	Bottom Contact	600 nm GaAs $n=2 \times 10^{18} \text{cm}^{-3}$
	Substrate	350 nm (100) Semi-Insulating GaAs

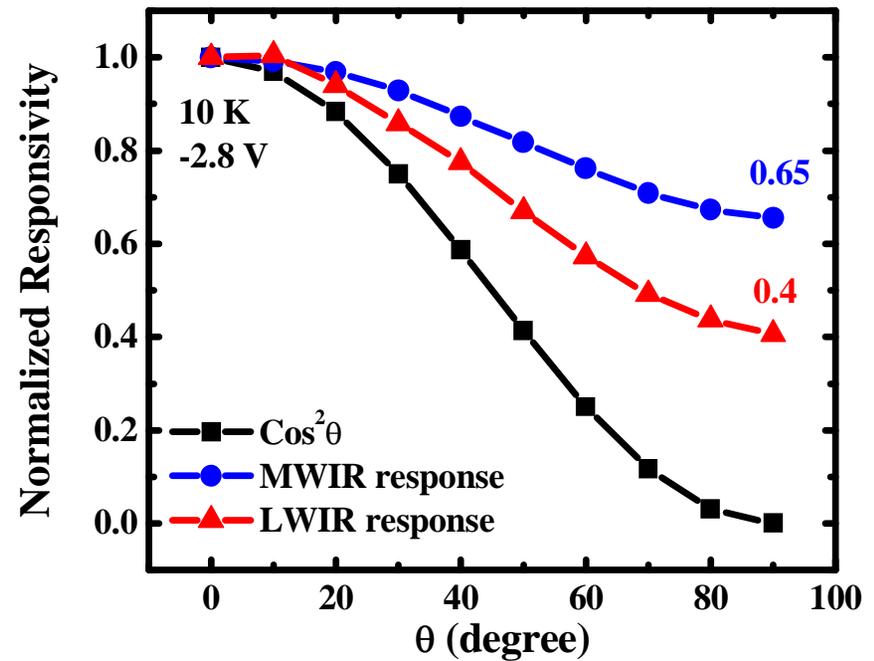
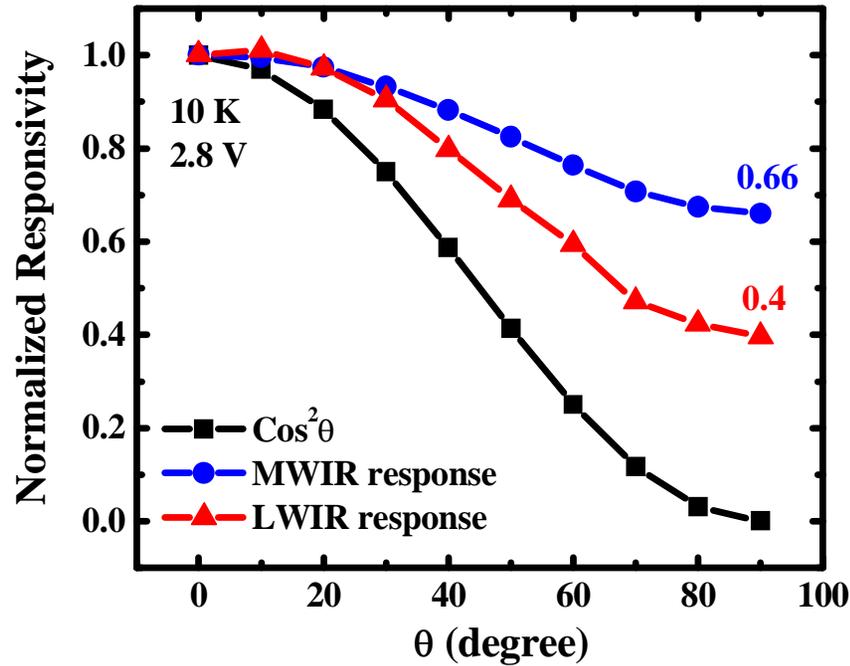


The Spectral Responses of The MMIP



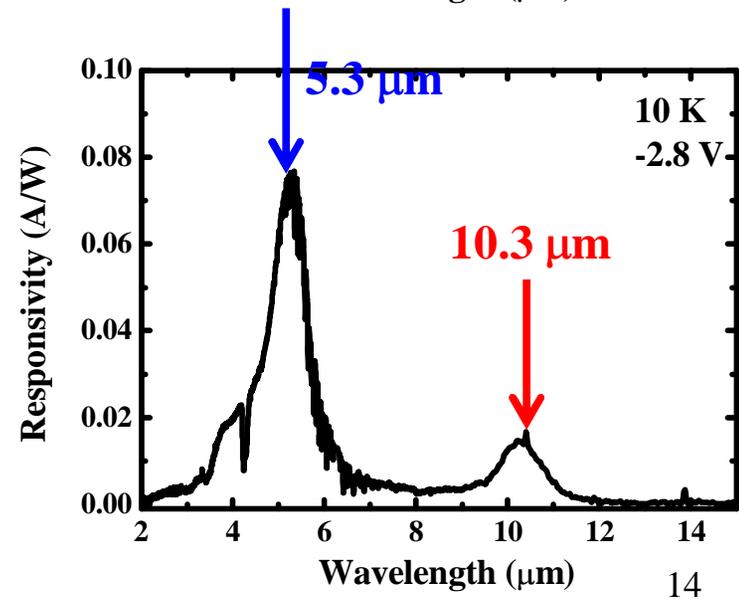
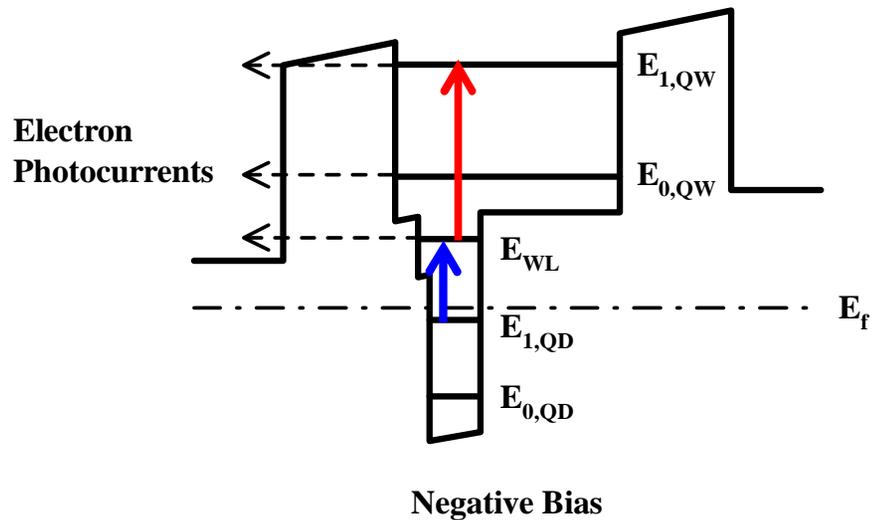
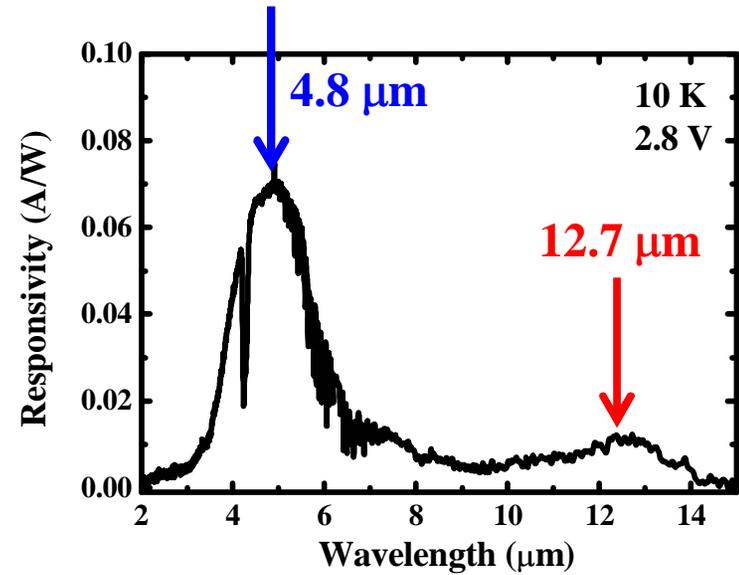
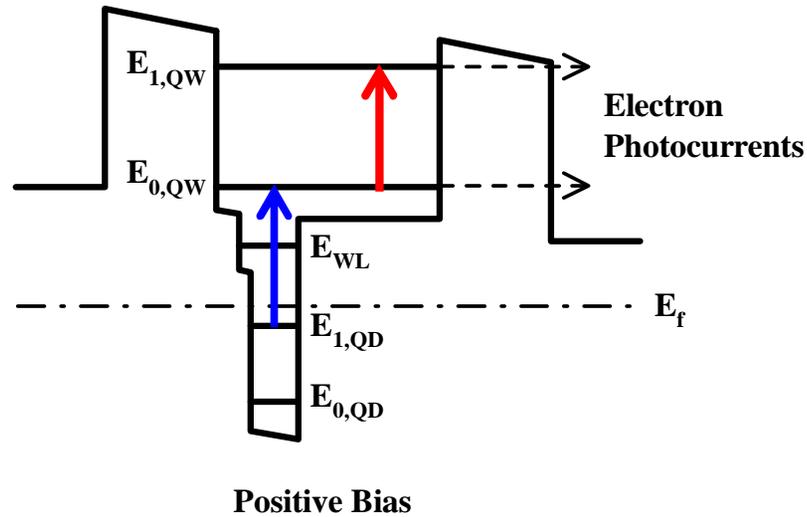


Normalized Responsivities over Different Polarized Lights





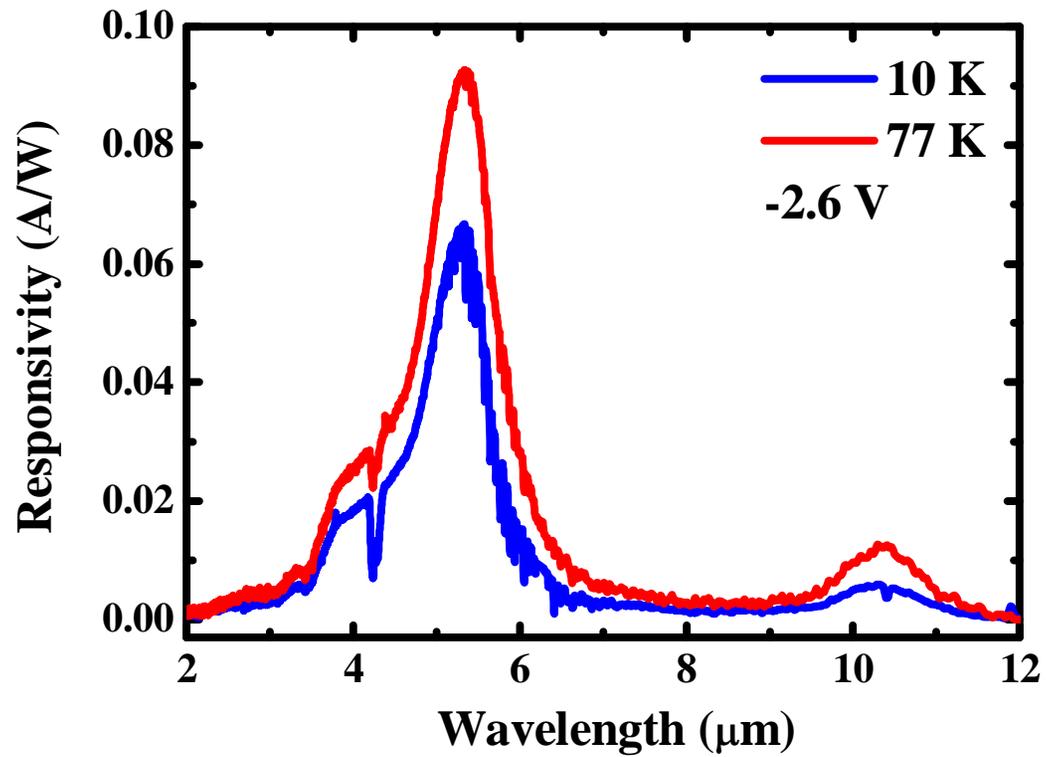
The Device Model of The MMIP



→
Growth Direction

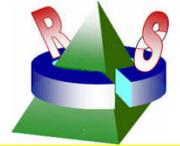


High-Temperature Operation of the MMIP





Conclusions



- **MWIR and LWIR Detections Are Observed within A Single Structure**
 - Multi-color detections at both MWIR and LWIR regions within a single device structure at the same applied voltage

- **The Increase of Photo-responses at LWIR with Increasing Temperatures**
 - High-temperature operation at both MWIR and LWIR regions

- **No Significant Normal Incident Absorption Observed at LWIR Region**
 - The responses at QD and QW regions are separate



Future Work



- **Wavelength Tuning at The LWIR Range**
 - The influence of barrier height on the detection wavelengths

- **The Effect of The (AlGa)As Barrier Width on The Device Performances**
 - The enhancement of LWIR responses for high-temperature operation